

AMENDMENTS TO THE ABSTRACT:

Please cancel the current abstract and insert the following.

-- An exposure apparatus has an optical system and transfers a pattern of a mask to a substrate via the optical system. The apparatus includes a structure, a partition wall which defines a space including an optical path of the optical system, and an elastic seal member which couples the structure and the partition wall to seal the space. The elastic seal member is arranged so that a hollow cylinder is compressed in a direction of an axis of the hollow cylinder. The hollow cylinder, in an uncompressed state, includes a member undulated in a cross section perpendicular to the axis and a shape of the uncompressed-state hollow cylinder in the cross section being substantially uniform along the axis. --